In-situ SEM sample cleaning



- Mounted on SEM chamber (currently Sigma FESEM)
- Using low power Oxygen Plasma
- Clean SEM samples in the chamber right before imaging

the nanoFAB, Oct. 14, 2015





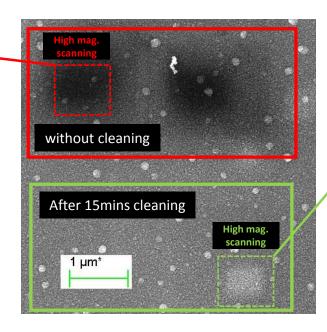
An environment designed for success.

without cleaning

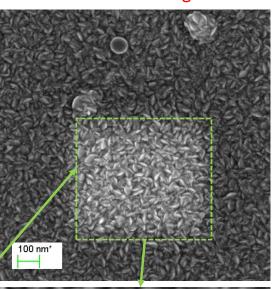
100 nm²

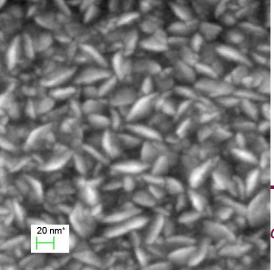
Test cleaning:

- Sample: ZnO film
- Cleaning: 35W O2 plasma for 15mins
- Microscope: Zeiss Sigma FESEM



after cleaning







ccess.